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12092 U. S. G. 1913 PRO

		Subclass	ISSUE CLASSIFICATION
	Class		

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**PATENT NUMBER**

**U.S. UTILITY Patent Application**

	<b>O.I.P.E.</b>	<b>PATENT DATE</b>
<b>SCANNED</b>	<b>1st 2</b>	<b>Q.A. Am</b>

APPLICATION NO.	CONT/PRIOR	CLASS	SUBCLASS	ART UNIT 2823 2812	EXAMINER J. O' M A N
09/843783		438			

## APPlicants

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Method to increase carbon and boron doping concentrations in Si and SiGe films

PTO-2040  
12/89

**ISSUING CLASSIFICATION**

<input type="checkbox"/> TERMINAL DISCLAIMER	DRAWINGS			CLAIMS ALLOWED	
	Sheets Drwg.	Figs. Drwg.	Print Fig.	Total Claims	Print Claim for O.G.
<input type="checkbox"/> The term of this patent subsequent to _____ (date) has been disclaimed.				NOTICE OF ALLOWANCE MAILED	
<input type="checkbox"/> The term of this patent shall not extend beyond the expiration date of U.S Patent. No. _____				ISSUE FEE	
				Amount Due	Date Paid
<input type="checkbox"/> The terminal ____ months of this patent have been disclaimed.				ISSUE BATCH NUMBER	

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